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FORM PTO-1449	SERIAL NO.	CASE NO.
	Not yet assigned	10808/200
LIST OF PATENTS AND PUBLICATIONS FOR	FILING DATE	GROUP ART UNIT
APPLICANT'S INFORMATION DISCLOSURE	Herewith	Not yet assigned
STATEMENT		
(use several sheets if necessary)	APPLICANT(S): Hin-Yiu Chung	et al.

REFERENCE DESIGNATION	U.S. PATENT DOCUMENTS
REFERENCE DESIGNATION	U.S. PATENT DUCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER Number-Kind Code (if known)	DATE	NAME	CLASS/ SUBCLASS	FILING DATE
/MDH./	A1	US 2002/0026900 A1	March 7, 2002	Huang et al.		
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/MDH./	A8	GB 2 355 850 A	May 2, 2001	United Kingdom		
8	A9	WO 99/03141	January 21, 1999	WO		
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EXAMINER INITIAL	svn	OTHER ART – NON PATENT LITERATURE DOCUMENTS nclude name of author, title of the article (when appropriate), title of the item (book, magazine, journal, serial, nposium, catalog, etc.), date page(s), volume-issue number(s), publisher, city and/or country where published.
/MDH./	A13	Spezialgraphite von SGL Carbon, Produkte für die Halbleitertechnik, SGL Carbon Group, pgs. 2-17, March 2001
200000000000000000		H.Q. Jia, H. Chen, W.C. Wang, W.X. Wang, W. Li, Q. Huang and Jiunming Zhou, <i>The Study of Thermal Stability During Wet Oxidation of AIAS</i> , Institute of Physics, Chinese Academy of Sciences, pgs. 484-488, Journal of Crystal Growth, Vol. 223, Issue 4, March 2001.
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\/	A16	Copy of International Search Report from International Application Number PCT/DE/02523. 7/26
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